

IN THE CLAIMS

Please amend the claims as follows:

Claim 1-10 (Cancelled).

Claim 11 (Currently Amended): A substrate processing apparatus comprising:

a processing vessel that defines a processing space therein;

a transparent case made of quartz, the transparent case including a cylinder portion and a top plate covering a top part of the cylinder portion;

a heating element, contained inside the transparent case, to generate heat inside the transparent case that heats for heating a substrate introduced into the processing space to a predetermined temperature;

~~a transparent case made of quartz, the transparent case including a cylinder portion and a top plate for containing the heating element;~~

a heater plate, mounted on an upper external surface of the top plate of the transparent case, to transmit the heat generated inside the transparent case to the substrate; and

a holding member having an axis penetrating the top plate of the transparent case and the heater plate and projecting from an upper surface of the heater plate, the axis having a plurality of arm portions to hold the substrate at a position spaced from and opposite to the upper surface of the heater plate located below the substrate; for holding the substrate at a position spaced from and opposite to the heater plate;

~~wherein the heater plate is mounted on an upper external surface of the transparent case and is arranged to be slightly separated from the top plate.~~

Claim 12 (Previously Presented): The substrate processing apparatus as claimed in claim 11, further comprising:

a depressurizing part for depressurizing an internal space of the processing vessel and an internal space of the transparent case at a same time.

Claim 13 (Previously Presented): The substrate processing apparatus as claimed in claim 11, further comprising:

a heat reflecting member provided below the heating element for upwardly reflecting heat from the heating element.

Claim 14 (Previously Presented): The substrate processing apparatus as claimed in claim 13, wherein the heat reflecting member is clamped below the heating element in an opposing state.

Claim 15 (Previously Presented): The substrate processing apparatus as claimed in claim 11, further comprising:

a gas injection part for injecting a gas from one side of the processing vessel to the substrate held by the holding member; and

an evacuation port provided at another side of the processing vessel for evacuating the gas passed through the substrate.

Claim 16 (Previously Presented): The substrate processing apparatus as claimed in claim 11, further comprising:

an ultraviolet source for irradiating ultraviolet rays to the processing space.

Claim 17 (Previously Presented): The substrate processing apparatus as claimed in claim 16, wherein the ultraviolet source is arranged to irradiate ultraviolet rays to an area half of the processing space.

Claim 18 (Previously Presented): The substrate processing apparatus as claimed in claim 11, wherein the transparent case includes a support bridge portion extending across the inside of the cylinder portion.

Claim 19 (Previously Presented) The substrate processing apparatus as claimed in claim 11, wherein the holding member includes:

a plurality of arm portions configured to support the substrate, and  
an axis having one end supporting the plural arm portions and another end inserted into the transparent case.

Claim 20 (Previously Presented) The substrate processing apparatus as claimed in claim 19, further comprising a rotational drive part configured to rotatively drive the axis of the holding member.

Claim 21 (Previously Presented) The substrate processing apparatus as claimed in claim 11, wherein the holding member includes a plurality of arm portions configured to support the substrate and an axis configured to support the plural arm portions, wherein the plural arm portions are formed of a transparent quartz and extend horizontally in radial directions from an upper end of the axis.

Claim 22 (Previously Presented) The substrate processing apparatus as claimed in claim 19, wherein the axis of the holding member is formed of an opaque quartz.

Claim 23 (Previously Presented) The substrate processing apparatus as claimed in claim 21, wherein the axis of the holding member is formed of an opaque quartz.

Claim 24 (Previously Presented) The substrate processing apparatus as claimed in claim 13, wherein the heat reflecting member is formed of an opaque quartz.

Claim 25 (Previously Presented): The substrate apparatus as claimed in claim 11, wherein the heater plate is separated from the top plate by a plurality of bosses.